

## Remarks

Applicant respectfully requests entry of the above amendment and reconsideration in view of the amendment and the following remarks.

The status of the application is as follows. Claims 1-8 remain pending in the application. The Examiner has objected to claim 1 for allegedly containing informalities. Claims 1-2 and 8 stand rejected under 35 U.S.C. §102(b) as allegedly being anticipated by US 4,024,835 to *Scheu et al.* Claims 3-6 stand rejected under 35 U.S.C. §103 as allegedly being unpatentable over *Scheu et al.* Claim 7 stands rejected under 35 U.S.C. §103 as allegedly being unpatentable over *Scheu et al.* in view of US 6,012,858 to *Konishi et al.* Applicant respectfully traverses the §102 and §103 rejections with the following arguments.

### ***Claim Objections***

Claim 1 is objected to for allegedly containing informalities. Claim 1 is amended herein for clarification. No new matter is believed added.

### ***Rejections under 35 U.S.C. §102***

Claims 1-2 and 8 stand rejected under 35 U.S.C. §102(b) as anticipated by *Scheu et al.*

*Scheu et al.* relates to a spinner chuck having a recessed portion for receiving non-circular substrates which is used to alleviate uneven build-up of photoresist coatings applied to the substrate. The spinner chuck receives the substrate in such a manner that a gap is left between the edge(s) of the substrate and the spinner chuck. The gap is an essential feature of *Scheu et al.* since “[s]ome resist flows into the gap between spinner chuck 310 and substrate 115.” (See col. 2, lines 20-21). This resist is subsequently removed via “resist drainage holes 315 which maybe provided to prevent build-up of resist material in the gap between substrate 115 and spinner chuck 315.” (See col. 2, lines 22-24).

The Examiner alleges that *Scheu et al.* discloses applying photoresist liquid onto a first surface of a substrate and rotating the substrate to spread the liquid. The Examiner also contends that *Scheu et al.* teaches that the substrate is received in a recessed area of the spin chuck,

whereby the depth of the recessed portion is approximately equal to the thickness of the substrate, thus providing an essentially flat or flush surface between the substrate and the spin chuck.

Applicant respectfully maintains that *Scheu et al.* does not disclose each and every feature of Applicant's invention as claimed in amended independent claim 1, as is required by 35 U.S.C. §102. Specifically, *Scheu et al.* does not disclose a method of manufacturing a circular optical storage disc, comprising, *inter alia*, providing a substrate present in an extension body, "the extension body having substantially circumferential contact with the periphery of the substrate, **wherein said substantially circumferential contact limits fluid flow therebetween to, at most, capillary flow**" (emphasis added). As defined in the specification, "substantially circumferential contact" is required to avoid "chinks between the extension body and the substrate." (See specification, page 3, lines 7-13). A "chink" is commonly defined as a narrow opening, such as a crack or fissure. Thus, in Applicant's method any space, between the outer edge or periphery of the substrate and the extension body in which the substrate is located, is either eliminated entirely or kept to a minimum such that any fluid flow between the extension body and the substrate is limited to no more than capillary flow. In contrast, *Scheu et al.* discloses a combination structure comprising a substrate 115 and a spinner chuck 310 wherein there must exist a gap between the periphery of the substrate and the spinner chuck. This gap is intended to receive excess liquid which flows off from the upper surface of the substrate as the spinner chuck is rotated.

Applicant maintains that the "gap" feature of *Scheu et al.* clearly precludes the space between the extension body and the substrate from limiting "fluid flow therebetween to, at most, capillary flow" as required by amended claim 1. Thus, Applicant respectfully submits that amended claim 1 patentably distinguishes over *Scheu et al.* Withdrawal of this rejection is respectfully requested.

Dependent claims 2 and 8, which depend from independent claim 1 and incorporate all the limitations of claim 1, for the reasons discussed above, patentably distinguish over *Scheu et al.* Withdrawal of this rejection is respectfully requested.

***Rejections under 35 U.S.C. §103***

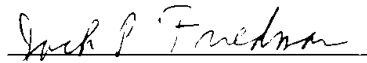
Claims 3-6 stand rejected under 35 U.S.C. §103(a) as allegedly being unpatentable over *Scheu et al.* Since claims 3-6 depend from claim 1, which Applicant has argued *supra* to be patentable under 35 U.S.C. §102, Applicant maintains that claims 3-6 are not unpatentable under 35 U.S.C. §103(a). Withdrawal of this rejection is respectfully requested.

Claim 7 stands rejected under 35 U.S.C. §103(a) as allegedly being unpatentable over *Scheu et al.* in view of *Konishi et al.* Since claim 7 depends from claim 1, which Applicant has argued *supra* to be patentable under 35 U.S.C. §102, Applicant maintains that claim 7 is not unpatentable under 35 U.S.C. §103(a). Withdrawal of this rejection is respectfully requested.

**Conclusion**

Accordingly, based on the preceding arguments, Applicant respectfully submits that claims 1-8, and the entire application, are in condition for allowance and therefore request favorable action. However, should the Examiner believe anything further is necessary in order to place the application in better condition for allowance, or if the Examiner believes that a telephone interview would be advantageous to resolve the issues presented, the Examiner is invited to contact the Applicant's undersigned representative at the telephone number listed below.

Respectfully submitted,



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